

INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)		ATTY DOCKET NO.	SERIAL NO.
		ITL.1054US(P17790)	10/695,103
		APPLICANT(S):	Huey-Chiang Liou et al.
		FILING DATE:	GROUP ART UNIT:
October 28, 2003		2823	

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
AA						
AB						
AC						
AD						
AE						
AF						
AG						
AH						
AI						

FOREIGN PATENT DOCUMENTS

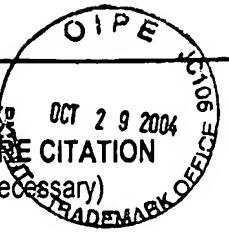
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
						YES
AJ						
AK						
AL						
AM						
AN						
AO						
AP						

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

T-D	AQ	S. Elhadj, J. W. Woody, V. S. Niu and R. F. Saraf, <i>Orientation of self-assembled block copolymer cylinders perpendicular to electric field in mesoscale film</i> , Applied Physics Letters, vol. 82, no. 6, 10 Feb. 2003, p. 871-3.
T-D	AR	Huiwen Liu, Bharat Bhushan, <i>Orientation and relocation of biphenyl thiol self-assembled monolayers under sliding</i> , Ultramicroscopy, vol. 91, no. 1-4, May 2002, p. 177-83.
T-D	AS	Sang Jung Ahn, Yun Kyeong Jang, Haeseong Lee, and Haiwon Lee, <i>Mechanism of atomic force microscopy anodization lithography on a mixed Langmuir-Blodgette resist of palmitic acid and hexadecylamine on silicon</i> , Applied Physics Letters, vol. 80, no. 14, 8 April 2002, p. 2592-4.
T-D	AT	Tiesheng Li, Masaya Mitsuishi, and Tokuji Miyashita, <i>Photodegradable polymer LB films for nanolithographic imaging techniques</i> , Thin Solid Films, vol. 389, no. 1-2, 15 June 2001, p. 267-71.

EXAMINE	T. DANG	DATE CONSIDERED
		11/23/04

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITATION <small>(Use several sheets if necessary)</small>			 <small>TRADEMARK OFFICE 9012</small>	ATTY DOCKET NO. ITL.1054US(P17790)	SERIAL NO. 10/695,103
			APPLICANT(S): Huey-Chiang Liou et al.		
			FILING DATE: October 28, 2003	GROUP ART UNIT: 2823	
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)					
T. D	BA	N.G. Semaltianos, H. Araujo, and E.G. Wilson, <i>Polymerization of Langmuir-Blodgett films of diacetylenes</i> , Surface Science, vol. 460, no. 1-3, 20 July 2000, p. 182-9.			
T. D	BB	Hiroyuki Sugimura, Atsushi Hozumi and Osamu Takai, <i>Fabrication of Coplanar Microstructures Composed of Multiple Organosilane Self-Assembled Monolayers</i> , IEICE Transactions on Electronics, vol. E83-C, no. 7, July 2000, p. 1099-103.			
T. D	BC	M. Sundermann, J. Hartwich, K. Rott, D. Meyners, E. Majkova, U. Kleineberg, M. Grunze, U. Heinzmann, <i>Nanopatterning of Au absorber films on Mo/Si EUV multilayer mirrors by STM lithography in self-assembled monolayers</i> , Surface Science, vol. 454-456, 20 May 2000, p. 1104-9.			
T. D	BD	Richard D. Peters, Xiao M. Yang, Tae K. Kim, B. H. Sohn, and Paul F. Nealey, <i>Using Self-Assembled Monolayers Exposed to X-rays To Control the Wetting Behavior of Thin Films of Diblock Copolymers</i> , Langmuir, vol. 16, no. 10, 16 May 2000, p. 4625-31.			
T. D	BE	Hiroyuki Sugimura, Kazuya Ushiyama, Atsushi Hozumi, and Osamu Takai, <i>Micropatterning of Alkyl- and Fluoroalkylsilane Self-Assembled Monolayers Using Vacuum Ultraviolet Light</i> , Langmuir, vol. 16, no. 3, 8 Feb. 2000, p. 885-8.			
T. D	BF	Hiroyuki Maruyama, Nobuyuki Kosai, Tadatake Sato, Shigehito Sagisaka, Hiroshi Segawa, Takeo Shimidzu and Kazuyoshi Tanaka, <i>Nanometer-Scale Lithography on the Oligosilane Langmuir-Blodgett Film</i> , Japanese Journal of Applied Physics, Part 1, vol. 36, no. 12A, Dec. 1997, p. 7312-16.			
T. D	BG	Chang Nam Kim, Dong Woo Kang, Eung Ryul Kim, and Haiwon Lee, <i>Fabrication of a Polymethylphenylmethacrylate Resist by Using Electron Beam Lithography</i> , Journal of the Korean Physical Society, vol. 31, no. 1, July 1997, p. 154-7.			
T. D	BH	T. Sato, and H. Ahmed, <i>Observation of a Coulomb staircase in electron transport through a molecularly linked chain of gold colloidal particles</i> , Applied Physics Letters, vol. 70, no. 20, 19 May 1997, p. 2759-61.			
T. D	BI	Earl T. Ada, Luke Hanley, Sergei Etchin, John Melngailis, Walter J. Dressick, Mu-San Chen and Jeffrey M. Calvert, <i>Ion beam modification and patterning of organosilane self-assembled monolayers</i> , Journal of Vacuum Science & Technology B, vol. 13, no. 6, Nov.-Dec. 1995, p. 2189-96.			
	BJ				
	BK				
	BL				
	BM				
	BN				
	BO				
	BP				
	BQ				
EXAMINER T. DANG			DATE CONSIDERED 11/23/04		
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>					